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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/708,983	04/05/2004	Jui-Tsen Huang	NAUP0487USA1	2982
27765	7590 12/29/2005	EXAMINER		
NORTH AMERICA INTELLECTUAL PROPERTY CORPORATION P.O. BOX 506			DUDA, KATHLEEN	
	MERRIFIELD, VA 22116		ART UNIT	PAPER NUMBER
	•		1756	
			DATE MAILED: 12/29/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

			- 41
	Application No.	Applicant(s)	
Office Action Commons	10/708,983	HUANG, JUI-TSEN	
Office Action Summary	Examiner	Art Unit	
	Kathleen Duda	1756	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address	
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 16(a). In no event, however, may a reply be time Till apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D. (35 U.S.C. § 133).	
Status			
1) ☐ Responsive to communication(s) filed on 2a) ☐ This action is FINAL. 2b) ☑ This 3) ☐ Since this application is in condition for alloware closed in accordance with the practice under E	- action is non-final. ice except for formal matters, pro		
Disposition of Claims	x parte Quayle, 1900 C.D. 11, 40	3 O.G. 213.	
4) Claim(s) 1-7 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw 5) Claim(s) is/are allowed. 6) Claim(s) 1-7 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or Application Papers 9) The specification is objected to by the Examiner 10) The drawing(s) filed on is/are: a) acceed to the description of	election requirement. r. epted or b) objected to by the Edrawing(s) be held in abeyance. See on is required if the drawing(s) is objected to by the left and the drawing(s) is objected to by the left and the drawing(s) is objected to by the left and the drawing(s) is objected to by the left and the lef	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 04202004.	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:		

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DETAILED ACTION

Claim Objections

1. Claim 5 is objected to because of the following informalities: the phrase "and the less" is not correct, perhaps "and less". Appropriate correction is required.

Claim Rejections - 35 USC § 112

2. Claim 5 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. Claim 5 recites that the photoresist absorbs light with a wavelength of "248 nm and the less". The specification teaches that the light is UV while the range recited covers wavelengths outside of that taught by the specification.

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Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 4. Claims 1-7 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Bruce (US Patent 4,978,594).

Bruce teaches a process of forming a pattern photolithographically. Example 1 teaches the process whereby a silicon wafer (claim 7) is cleaned and a layer of polymer is applied (first organic layer). A sacrificial layer of silicon nitride is applied (claim 4) followed by a fluorine-containing polymer and a photoresist layer. The photoresist is exposed to ultraviolet light (encompassed by the range recited in claim 5) and developed to form an etching mask. An oxygen plasma (claim 3) is then used to etch the fluorine-polymer layer followed by etching the silicon nitride layer. Figure 2 depicts the layers as applied before processing occurs.

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Conclusion

5. Any inquiry concerning this communication should be directed to Examiner K. Duda at (571) 272-1383. Official FAX communications should be sent to (571) 273-8300.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor; Mark Huff, can be reached at 571-272-1385.

Information regarding the status of an application may be obtained from the Patent Application Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Kathleen Duda Primary Examiner Art Unit 1756